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APPLICATION NO.	FILI	ING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/698,875	10	/31/2003	Bulent M. Basol	NT-286-US	2008
7	590	08/02/2005	•	EXAM	INER
NuTool, Inc.		• /	DOLAN, JENNIFER M		
Legal Departm 1655 McCandl		;		ART UNIT	PAPER NUMBER
Milpitas, CA		•		2813	
				DATE MAILED: 08/02/200	5

Please find below and/or attached an Office communication concerning this application or proceeding.

RECEIVED RECIPENAP AUG 2 6 2005

	Application No.	Applicant(s)	
Office Action Summers	10/698,875	BASOL ET AL.	(fer
Office Action Summary	Examiner	Art Unit	
	Jennifer M. Dolan	2813	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence ad	dress
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	16(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) day fill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timel the mailing date of this c D (35 U.S.C. § 133).	y. ommunication.
Status			
1) Responsive to communication(s) filed on 23 Ma	av 2005.	·	
	action is non-final.		
3) Since this application is in condition for allowan	ice except for formal matters, pro	secution as to the	e merits is
closed in accordance with the practice under E			
Disposition of Claims			
4) Claim(s) <u>1-32</u> is/are pending in the application.			
4a) Of the above claim(s) <u>5.6,9-18 and 20-32</u> is	/are withdrawn from consideration	an .	•
5) Claim(s) is/are allowed.	and with and with morn definition and	····	
6)⊠ Claim(s) <u>1-4,7,8 and 19</u> is/are rejected.			
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and/or	election requirement.		•
Application Papers			
9)☐ The specification is objected to by the Examiner		•	
10) The drawing(s) filed on 23 May 2005 is/are: a)		ov the Evaminer	
Applicant may not request that any objection to the o		•	
Replacement drawing sheet(s) including the correcti		• •	FR 1 121(d)
11) The oath or declaration is objected to by the Ex			
Priority under 35 U.S.C. § 119			
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priori application from the International Bureau * See the attached detailed Office action for a list of 	s have been received. s have been received in Applicati ity documents have been receive (PCT Rule 17.2(a)).	on No ed in this National	Stage
Attachment(s)			
1) Notice of References Cited (PTO-892)	4) Interview Summary		
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 3/22/04.	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:)-152)

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DETAILED ACTION

Election/Restrictions

1. Claims 5, 6, 9-18, and 20-32 have been withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim. Election was made without traverse in the reply filed on 5/23/05.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1-4 and 19 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 4,968,375 to Sato et al.

Regarding claims 1, 2, and 19, Sato discloses a method of removing a conductive material from an edge region of a workpiece/semiconductor IC device (see column 1, lines 5-15; column 2), comprising: supplying an etch solution to create an etchant bead (column 6, lines 14-18) at a contoured opening (21a) of an edge removal device (figure 2a); contacting the edge region of the workpiece with the etchant bead (column 3, lines 17-50; column 6, lines 14-30);

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and establishing relative motion between the workpiece and the edge removal device to remove the conductive material from the edge region of the workpiece (column 5, lines 15-35; column 6, lines 5-14), where the etchant bead is maintained at the opening of the removal device (column6, lines 14-17).

Regarding claims 3 and 4, Sato discloses that the edge removal device comprises a cavity (21a) having the opening, such that the edge of the workpiece is inserted into the cavity and the etch solution contacts the top, bottom, and side of the workpiece (figures 2a, 2b; column 3, lines 30-50).

4. Claims 1-4 and 19 are rejected under 35 U.S.C. 102(e) as being anticipated by U.S. Patent No. 6,523,553 to Redeker et al.

Regarding claims 1, 2, and 19, Redeker discloses a method of removing a conductive material (column 1, lines 50-52) from an edge region of a workpiece/semiconductor IC (column 2, lines 5-45; 60-67) comprising the steps: supplying an etch solution (column 5, lines 5-25) to create an etchant beat at a contoured opening (31) of an edge removal device (figure 2); contacting the edge region of the workpiece with the etchant bead (column 5, lines 34-46); and establishing relative motion between the workpiece and the edge removal device to remove the conductive material from the edge of the workpiece (column 5, lines 36-42), where the edge bead is maintained at the opening (column 5, lines 9-14; etchant supply and outlet lines maintain the edge bead).

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Regarding claims 2 and 3, Redeker discloses a cavity (31), where the edge of the workpiece is inserted into the cavity (figure 2), and where the etch solution contacts the top, bottom, and side of the workpiece (figure 2; column 5).

Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 7 and 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sato et al. in view of U.S. Patent No. 6,550,091 to Radman et al.

Sato fails to disclose that the cavity includes a spongy material, where the edge region of the workpiece is contacted with the spongy material.

Radman discloses a method for scrubbing the edge portions of a wafer, wherein the cavity includes etchant solution and a spongy material (230) that contacts the workpiece (see column 5, lines 15-47; figures 3b; 4; 5).

It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the method of Sato, such that a spongy material contacting the workpiece edges is included, as suggested by Radman. The rationale is as follows: A person having ordinary skill in the art would have been motivated to include a spongy material, because Radman teaches that the combination of applying an etching solution and scrubbing the wafer

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with a pliable pad material will aid in removing undesired metal deposits and will more efficiently clean the wafer (see Radman, column 3, lines 1-10; column 5, lines 15-45; column 6, lines 22-27).

Conclusion

- 7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
 - a. U.S. Patent No. 6,063,232 to Terasawa et al. teaches polishing a wafer by applying a foam scrubbing member and a bead of etchant solution in a cavity.
 - b. U.S. Patent No. 5,868,857 to Moinpour et al. discloses using pads and etchantsupply nozzles for cleaning the periphery of a wafer.
 - c. U.S. Patent No. 5,608,943 to Konishi et al. discloses an apparatus for cleaning the bottom outer periphery of a semiconductor wafer.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jennifer M. Dolan whose telephone number is (571) 272-1690. The examiner can normally be reached on Monday-Friday 8:30am-5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl W. Whitehead, Jr. can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Jennifer M. Dolan Examiner Art Unit 2813

imd

LAURA M. SCHILLINGER PRIMARY EXAMINER



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Basol et al.

Group Art Unit: 2812

Examiner: Not yet assigned

Docket: NT-286-US

Serial No.: 10/698,875

Filed: October 31, 2003

Title: Method And Device To Remove

Unwanted Material From The Edge Region Of

A Workpiece

INFORMATION DISCLOSURE STATEMENT

US PATENT DOCUMENTS

	Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	
4	MID	AA	US-6,494,219	Dec., 2002	Nayak et al.	Copy Enclosed
ł	MUS	AB	US-2001/0052159	Dec., 2001	Moinpour et al.	Copy Enclosed
	Chis	AC	US-6,309,981	Oct., 2001	Mayer et al.	Copy Enclosed
ľ	MI	AD	US-6,056,869	May, 2000	Uzoh	Copy Enclosed

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant		
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OTHER DOCUMENTS

Examiner Initials	Cite No.		Trans- lation

Examiner Signature Date Considered 7/29/05

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Application/Control No. Notice of References Cited Application/Control No. 10/698,875 Examiner Jennifer M. Dolan Applicant(s)/Patent Under Reexamination BASOL ET AL. Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-4,968,375	11-1990	Sato et al.	156/345.23
	В	US-6,523,553	02-2003	Redeker et al.	134/61
	С	US-6,550,091	04-2003	Radman et al.	15/77
	D	US-6,063,232	05-2000	Terasawa et al.	156/345.23
	Ε	US-5,868,857	02-1999	Moinpour et al.	134/6
	F	US-5,608,943	03-1997	Konishi et al.	15/302
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FOREIGN PATENT DOCUMENTS

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	Z					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

NEW CENTRAL FAX NUMBER

Effective July 15, 2005

On <u>July 15, 2005</u>, the Central FAX Number will change to **571-273-8300**. This new Central FAX Number is the result of relocating the Central FAX server to the Office's Alexandria, Virginia campus.

Most facsimile-transmitted patent application related correspondence is required to be sent to the Central FAX Number. To give customers time to adjust to the new Central FAX Number, faxes sent to the old number (703-872-9306) will be routed to the new number until September 15, 2005. After September 15, 2005, the old number will no longer be in service and 571-273-8300 will be the only facsimile number recognized for "centralized delivery".

CENTRALIZED DELIVERY POLICY: For patent related correspondence, hand carry deliveries must be made to the Customer Service Window (now located at the Randolph Building, 401 Dulany Street, Alexandria, VA 22314), and facsimile transmissions must be sent to the Central FAX number, unless an exception applies. For example, if the examiner has rejected claims in a regular U.S. patent application, and the reply to the examiner's Office action is desired to be transmitted by facsimile rather than mailed, the reply must be sent to the Central FAX Number.

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